

## AMENDMENTS TO THE CLAIMS

### 1-5. (Cancelled)

**6. (Currently Amended)** A method for manufacturing a plasma display panel (PDP) including a process for forming a metal oxide film onto a substrate of the PDP, the method comprising:

forming the metal oxide film in a deposition room having a degree of vacuum within a range of  $1 \times 10^{-1}$  Pa to  $1 \times 10^{-2}$  Pa; and

maintaining the degree of vacuum by

introducing inert gas into the deposition room during deposition of the metal oxide film,

reducing an oxygen deficiency in the deposition room by introducing oxygen into the deposition room during deposition of the metal oxide film,

increasing the oxygen deficiency in the deposition room by introducing at least one gas selected from the group consisting of oxygen, water, hydrogen, carbon monoxide, and carbon dioxide and inert gas into the deposition room during deposition of the metal oxide film, and wherein the oxygen or the at least one gas is introduced into the deposition room in a predetermined amount,

controlling amounts of the inert gas and the other of the oxygen or the at least one gas to be introduced into the deposition room, and

equilibrating an amount of gas the amounts of the gasses introduced into the deposition room and with an amount of gas exhausted from the deposition room by a vacuum exhausting system so as to control the oxygen deficiency in the deposition room within a predetermined range.

**7. (Currently Amended)** The method for manufacturing the PDP of claim 6, wherein the at least one gas includes oxygen, and wherein said maintaining of the degree of vacuum further comprises:

introducing at least one gas selected from the group consisting of water, hydrogen, carbon monoxide and carbon dioxide at a constant amount into the deposition room; and

adjusting an amount of the oxygen gas introduced into the deposition room.

**8. (Currently Amended)** The method for manufacturing the PDP of claim 6, wherein said introducing of at least one gas comprises introducing at least one gas selected from the group consisting of water, hydrogen, carbon monoxide and carbon dioxide, and wherein said maintaining of the degree of vacuum further comprises:

introducing an amount of oxygen at a constant value; and

adjusting an amount of the at least one gas selected from the group consisting of water, hydrogen, carbon monoxide and carbon dioxide introduced into the deposition room.

**9. (Currently Amended)** The method for manufacturing the PDP of claim 6, wherein the at least one gas includes inert gas, and wherein said maintaining of the degree of vacuum further comprises:

introducing at least one gas selected from the group consisting of oxygen, water, hydrogen, carbon monoxide and carbon dioxide at a constant value into the deposition room; and  
adjusting an amount of the inert gas introduced into the deposition room.

**10. (Currently Amended)** The method for manufacturing the PDP of claim 6, wherein said introducing of at least one gas comprises introducing oxygen gas and at least one gas selected from the group consisting of carbon dioxide and inert gas, and wherein said maintaining of the degree of vacuum further comprises:

adjusting an amount of the oxygen gas and the at least one gas selected from the group consisting of carbon dioxide and inert gas introduced into the deposition room.